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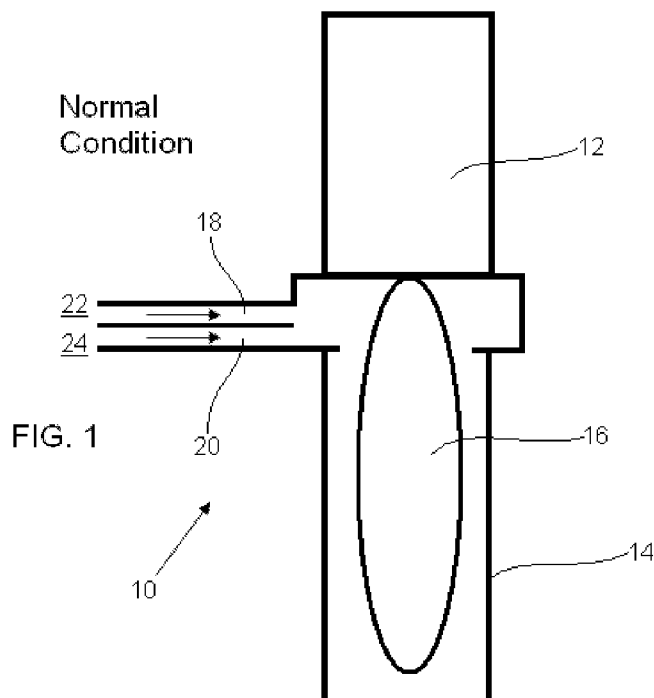
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(54) Title: APPARATUS FOR TREATING A GAS STREAM



(57) Abstract: The present invention provides apparatus for treating a gas stream (22). A plasma abatement device (10) has a reaction chamber (14) and a plasma torch (12) for generating a plasma stream for injection into the chamber for treating the gas stream. A first inlet (18) conveys a gas stream into the plasma abatement device for treatment, and a second inlet (20), in a normal condition of the apparatus, is in flow communication with a source of reagent for conveying reagent (24) into the plasma device for improving the efficiency of the treatment. In a back-up condition of the apparatus, the second inlet is in flow communication with a gas stream source for conveying a gas stream into the device for treatment.



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